Device and Method for Treatment of Substrate Surfaces

Abstract

A device for treatment of a substrate treatment surface (9o) of a substrate (9) with a fluid by immersion of the substrate treatment surface (9o) into the fluid (8), with the following features:

- receiving means (5) for receiving the fluid (8) with an immersion opening and
- immersion means (19) for immersion of the substrate treatment surfaces (9o) through the immersion opening (5e) into the receiving means (5),

is characterized in that there are rotation means (13) for rotation of the receiving means (5) for at least predominant discharge of the fluid (8) from the receiving means (5), as well as of a method for treatment of at least one substrate treatment surface (9o) of a substrate (9) with a fluid (8) with the following steps, especially following sequence:

- immersion of the substrate treatment surface(s) into the fluid (8) which is held in a receiving means (5) for receiving the fluid (8),
- rotation of the receiving means (5) for emptying the fluid out of the receiving means (5).

Figure 1